

Corres. and Mail

BOX AF

**RESPONSE UNDER 37 CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1752**

AF

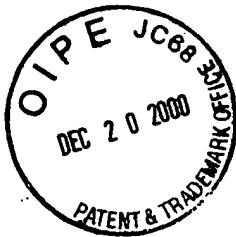
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Hiroshi TAKANASHI et al.

Serial No. 09/262,077

Filed March 4, 1999



Docket No. 01497/FP/TOK-16-US/YH

Group Art Unit 1752

Examiner S. Lee

NEGATIVE-WORKING PHOTORESISTIVE
RESIN COMPOSITION AND
PHOTORESISTIVE RESIN PLATE USING
THE SAME

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEE FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975.

13/CE1

RESPONSE TO FINAL REJECTION

Assistant Commissioner for Patents,
Washington, D.C.

Sir:

This is in response to the Final Rejection dated September 20, 2000.

REMARKS

Favorable reconsideration is respectfully requested.

The claims are 6 to 9.

Claims 6 to 9 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Pine (U.S. 4,361,640).

This rejection is respectfully traversed.

In claim 6 of the present application, component (E) is defined as being at least one member selected from compounds of the formula (I), i.e., R^1-X , but not limited to p-toluenesulfonamide and o-toluenesulfonamide. In support of such claim, there is submitted herewith a Declaration under 37 C.F.R. 1.132 of H. Takanashi, the first named inventor herein,

TECHNOLOGY CENTER 1700

DEC 22 2000

RECEIVED